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(54) Title (EN): FAST SUBSTRATE LOADING ON POLISHING HEAD WITHOUT MEMBRANE INFLATION STEP

(54) Title (FR): chargement rapide de substrat sur une tête de polissage sans étape de gonflement de membrane

(57) Abstract:

(EN): The present invention relates to an apparatus and method for improving and speeding up a substrate loading process. The apparatus (200) includes a base member (208) having a bottom surface (209) with a plurality of recesses (210) formed therein and passages (224,225) formed within to pump a control gas in or out. The apparatus also includes a flexible membrane (205) that forms a center chamber (206) and an edge chamber (207) that may be inflated and deflated independently. A substrate support (201) is used to load a substrate (202) on the apparatus.

(FR): La présente invention concerne un appareil et un procédé pour améliorer et accélérer un processus de chargement de substrat. Un mode de réalisation permet d'obtenir un procédé de serrage par ventouse d'un substrat. Le procédé comprend la ventilation d'une chambre centrale d'une membrane flexible configurée pour fixer le substrat, le déplacement du substrat de telle sorte qu'une face arrière du substrat est en contact total avec la membrane flexible et l'aspiration de la chambre centrale pour serrer par ventouse la face arrière du substrat sur la membrane flexible.

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